

<b>FORM PTO-1449</b>  <b>INFORMATION DISCLOSURE CITATION</b>		Attorney Docket: 1232-4590US2		Serial No.: to be assigned			
		Applicants: Yanagita et al.		Examiner: to be assigned			
		Filing Date: August 13, 2003		Group Art Unit: to be assigned			
<b>U.S. PATENT DOCUMENTS</b>							
Examiner Initial		Patent Number	Publication Date	Name	Class	Sub-Class	Filing Date
MAO	AA	3,493,155	02/03/70	Irving Litant et al.	225	2	
MAO	AB	3,549,446	12/22/70	R.W. Bennett et al.	156	230	
MAO	AC	3,667,661	06/06/72	Farmer	225	2	
MAO	AD	3,730,410	05/01/73	Altshuler	225	96.5	
MAO	AE	4,962,879	10/16/90	Goesele et al.	156	281X	
MAO	AF	5,100,544	03/31/92	Izutani, et al.	210	75	
MAO	AG	5,255,853	10/26/93	Munoz	83	177X	
MAO	AH	5,374,564	12/20/94	Bruehl	437	24	
MAO	AI	5,379,235	01/03/95	Fisher et al.	364	508	
<b>FOREIGN PATENT DOCUMENTS</b>							
Examiner Initial		Patent Number	Publication Date	Country	Class	Sub-Class	Translation
MAO	AJ	KR 1998-33377	0/75/98	Korean	—	—	<input type="checkbox"/> Yes <input type="checkbox"/> No
MAO	AK	EP 0 709 876 A1	05/01/96	Europe	—	—	<input type="checkbox"/> Yes <input type="checkbox"/> No
MAO	AL	EP 0 840 381 A2	05/06/98	Europe	—	—	<input checked="" type="checkbox"/> Yes <input type="checkbox"/> No
MAO	AM	EP 0 843 345 A2	5/20/98	Europe	—	—	<input type="checkbox"/> Yes <input type="checkbox"/> No
<b>OTHER DOCUMENTS (Including Author, Title, Date, etc.)</b>							
MAO	AN	"Single-Crystal Silicon on Non-Single-Crystal Insulators", G.W. Cullen, <u>Journal of Crystal Growth</u> , Vol. 63, No. 3, pp. 429-590, 1983					
MAO	AO	"Crystalline Quality of Silicon Layer Formed by FIPOS Technology", Kazuo IMAI et al., <u>Journal of Crystal Growth</u> , Vol. 63, pp 547-553, 1987					
MAO	AP	"Silicon-On-Insulator by Wafer Bonding: A Review", W.P. Maszara, <u>Journal of Electrochemical Society</u> , Vol. 138, pp. 341-347, 1991					
Examiner Mark A. Osele				Date Considered 5-27-04			
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Examiner Initial		Patent Number	Publication Date	Name	Class	Sub-Class	Filing Date
MAO	AQ	5,510,019	4/23/96	Yabumoto et al.	210	137	
MAO	AR	5,747,387	05/05/98	Koizumi et al.	438	906X	
MAO	AS	5,783,022	07/21/98	Cha et al.	156	344	
MAO	AT	5,849,602	12/15/98	Okamura et al.	438	908X	
MAO	AU	5,876,497	03/02/99	Atoji	117	85	
MAO	AV	5,928,389	7/27/99	Jevtic	29	25.01	
MAO	AW	5,934,856	08/10/99	Asakawa et al.	414	217	
MAO	AX	5,994,207	11/30/99	Henley et al.	438	515	02/19/98
MAO	AY	6,122,566	09/19/00	Nguyen et al.	438	908X	03/03/98

  

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Examiner Initial		Patent Number	Publication Date	Country	Class	Sub-Class	Translation
MAO	AZ	EP 0 999 578 A2	05/10/00	Europe	—	—	<input checked="" type="checkbox"/> Yes <input type="checkbox"/> No
MAO	BA	EP 1 026 729 A2	08/09/00	Europe	—	—	<input checked="" type="checkbox"/> Yes <input type="checkbox"/> No
MAO	BB	EP 1 045 448 A1	10/18/00	Europe	—	—	<input type="checkbox"/> Yes <input type="checkbox"/> No
MAO	BC	EP 0 926 719 A2	06/30/99	Europe	—	—	<input type="checkbox"/> Yes <input type="checkbox"/> No

  

OTHER DOCUMENTS (Including Author, Title, Date, etc.)		
MAO	BD	"Light Scattering Topography Characterization of Bonded SOI Wafer", H. Baumgart, et al., <u>Extended Abstracts</u> , Vol. 91-2, pp. 733-734, 1991
MAO	BE	"Thinning of Bonded Wafer: Etch-Stop Approaches", Charges E. Hunt et al., <u>Extended Abstracts</u> , Vol. 91-2, pp. 696-697, 1991
MAO	BF	"Epitaxial Layer Transfer by Bond and Etch Back of Porous Si", Takao Yonehara et al., <u>Applied Physics Letters</u> , Vol. 64, pp. 2108-2110, 1994
Examiner		Date Considered
Mark A. Oshe		5-27-04

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Examiner Initial		Patent Number	Publication Date	Name	Class	Sub-Class	Filing Date
MAO	BG	6,221,740	4/24/01	Bryan et al.	438	458	
MAO	BH	6,277,234 B1	8/21/01	Freund et al.	156	344	
MAO	BI	6,321,134 B1	11/20/01	Henley et al.	700	121	11/20/01
MAO	BJ	5,570,994	11/5/1996	Somekh et al.	414	786	5/10/1995
MAO	BK	2,191,513	2/27/40	W. P. Bigelow	141	7	3/13/37
MAO	BL	2,517,394	8/1/50	Z. U. Le Tellier	134	80	2/19/45
MAO	BM	3,094,207	6/18/63	R. G. Millhiser et al.	198	209	5/24/61
MAO	BN	3,489,608	1/13/70	B. Jacobs et al.	134	25	10/26/65
MAO	BO	3,970,471	7/20/76	Bankes et al.	134	6	4/23/75

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Examiner Initial		Document Number	Publication Date	Country	Class	Sub-Class	Translation
MAO	BP	5-21338	1/29/93	Japan	—	—	English Abstract
MAO	BQ	7-302889	11/14/95	Japan	—	—	English Abstract
MAO	BR	WO 99/06110	02/11/99	WO	—	—	<input type="checkbox"/> Yes <input type="checkbox"/> No
MAO	BS	WO 01/04933	01/18/01	WO	—	—	<input type="checkbox"/> Yes <input type="checkbox"/> No
MAO	BT	WO 01/10644 A1	02/15/01	WO	—	—	<input type="checkbox"/> Yes <input type="checkbox"/> No

### OTHER DOCUMENTS (Including Author, Title, Date, etc.)

MAO	BU	"Electrolytic Shaping of Germanium and Silicon", A. Uhlir et al., <u>Bell System Technical Journal</u> , Vol. 35, pp. 333-347, 1956
MAO	BV	"Oxidized Porous Silicon and It's Application", K. Nagano et al., <u>The Transactions of the Institute of Electronics and Communication Engineers. The Institute of Electronics, Information and Communication</u>
MAO	BW	"A New Dielectric Isolation Method Using Porous Silicon", K. Imai, <u>Solid -State Electronics</u> , Vol. 224, pp. 159-164, 1981

Examiner	Mark A. Osele	Date Considered	5-27-04
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Examiner Initial		Patent Number	Publication Date	Name	Class	Sub-Class	Filing Date
MAO	BX	4,047,973	9/13/77	Williams	134	10	10/27/76
MAO	BY	4,208,760	6/24/80	Dexter et al.	15	302	12/19/77
MAO	BZ	4,215,928	8/5/80	Bayley et al.	354	319	3/30/79
MAO	CA	4,850,381	7/25/89	Moe et al.	134	62	2/1/88
MAO	CB	5,248,886	9/28/93	Asakawa et al.	250	442.11	2/27/92
MAO	CC	5,357,645	10/25/94	Onodera	15	97.1	5/14/93
MAO	CD	5,653,247	8/5/1997	Murakami	134	80	8/14/95
MAO	CE	5,679,405	10/21/97	Thomas et al.	427	248.1	7/24/95
MAO	CF	5,792,709	8/11/98	Robinson et al.	438	692	12/19/95

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Examiner Initial		Patent Number	Publication Date	Country	Class	Sub-Class	Translation
MAO	CG	JPA 56-30650	3/27/81	Japan	✓	—	Abstract Only
MAO	CH	JPA60-05530	1/14/94	Japan	—	—	English Abstract
MAO	CI	JPA4-293236	10/16/92	Japan	✓	—	English Abstract

## OTHER DOCUMENTS (Including Author, Title, Date, etc.)

MAO	CJ	"Silicon on Insulator Material by Wafer Bonding", Christine Harendt, Charles E. Hunt et al., <i>Journal of Electronic Materials</i> , vol. 20, pp. 267-277, 1991
MAO	CK	Michel Bruel, et al. "Smart-Cut: A New Silicon On Insulator Material Technology Based On Hydrogen Implantation And Wafer Bonding", <i>Jpn. J. Appl. Phys. Vol. 36, No. 3B, Part 01, March 1, 1997, pages 1636-1641.</i>
MAO	CL	U.S. Application Serial No. 09/399,643, filed September 20, 2002, entitled "Separating Apparatus and Method, and Substrate Manufacturing Method."

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MAO	CM	5,795,401	8/18/98	Itoh et al.	134	6	10/10/96
MAO	CN	5,810,028	9/22/98	Ichikawa et al.	134	66	6/12/97
MAO	CO	5,820,329	10/13/98	Derbinski et al.	414	225	4/10/97
MAO	CP	5,954,888	9/21/99	Gupta et al.	134	3	2/9/98
MAO	CQ	6,007,675	12/28/99	Toshima	156	345	12/1/97
MAO	CR	6,168,499	1/2/2001	Jang	451	8	5/18/99
MAO	CS	4,915,564	4/10/90	Error et al.	414	217	7/20/98
MAO	CT	6,131,589	10/17/00	Vogtmann et al.	134	113	2/9/99
MAO	CU	6,382,292	5/7/02	Ohmi et al.	156	584	3/25/98
MAO	CV	6,418,999	7/16/02	Yanagita et al.	156	584	12/15/98
MAO	CW	6,527,031	3/4/03	Yanagita et al	156	584	11/5/99

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Examiner Initial		Patent Number	Publication Date	Country	Class	Sub-Class	Translation
MAO	CX	JPA63-16455	11/15/94	Japan	—	—	English Abstract
MAO	CY	JPA9-167724	6/24/97	Japan	—	—	English Abstract
	CZ						<input type="checkbox"/> Yes <input type="checkbox"/> No

## OTHER DOCUMENTS (Including Author, Title, Date, etc.)

MAO	DA	U.S. Application Serial No. 09/434,740, filed November 11, 2002, entitled "Sample Separating Apparatus and Method."
MAO	DB	U.S Application No. 09/434,663, filed November 5, 1999, entitled "Sample Processing System," to K. Yanagita et al.
MAO	DC	"History of Water Jet Machining Development", Journal of the Water Jet Technology Society of Japan, vol. 1, No. 1, 1984, pages 4-15.
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